



UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of : **Confirmation No. 8121**
Kazuyuki NITTA et al. : Docket No. 2001_1143A
Serial No. 09/928,430 : Group Art Unit 1752
Filed August 14, 2001 : Examiner S. Lee

POSITIVE-WORKING PHOTORESIST
COMPOSITION AND RESIST PATTERNING
METHOD USING SAME

RESPONSE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Official Action dated November 12, 2003, the period for response having been extended for two months by the attached Petition, please amend the present application as follows: